



## SMALL-SCALE INSTALLATION FOR FILM DEPOSITION BY MAGNETRON SPUTTERING

# MVU TM MAGNA 02

### Purpose:

Deposition of metal films and resistive materials by magnetron sputtering.

### Special characteristics:

- Type and quantity of magnetron sputtering device in the installation:  
DC magnetron sputtering device - 1 pc.
- Substrate processing in one technological cycle (single-sided processing):  
Ø 150 mm – 2 pcs.;
- Periodical half turn of substrate holder;
- Microprocessing control system;
- Oil-free pumping system (turbomolecular pump 60 l/h);
- Consumed power not more than 4,5 kW;
- 2,5 m<sup>2</sup> area per one installation.

